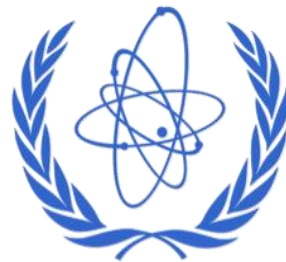


A tool for GIXRF/XRR simulation and data analysis

Vakula N.I., Leani J.J., Migliori A., Bogovac M.,
Padilla-Alvarez R., Kaiser R.B. and Karydas A.G.



IAEA

International Atomic Energy Agency



Introduction

Motivation:

The IAEA has developed a beamline end-station facility that it is currently installed at the newly developed XRF beamline of Elettra Sincrotrone Trieste, Italy

The end-station called Ultra High Vacuum Chamber (UHVC) is a multipurpose facility for applying simultaneously various complementary and advanced variants of X-Ray Spectrometry (XRS) techniques, including:

- Total Reflection X-ray Fluorescence Analysis (**TXRF**)
 - Grazing Incidence/Exit XRF analysis (**GIXRF- GEXRF**)
 - Near Edge X-ray Absorption Fine Structure (**NEXAFS**)
 - X-ray Reflectometry (**XRR**)
- The current development of GIXRF/XRR simulations/analysis tool aims at assisting end-users in data processing and interpretation

UHVC Instrumentation: 7-Axis Sample Manipulator

The sample manipulator includes:

Four (4) linear stages ('X', 'Y', 'Z', 'Diode')

Three (3) goniometers ('Theta/2Theta', 'Phi')

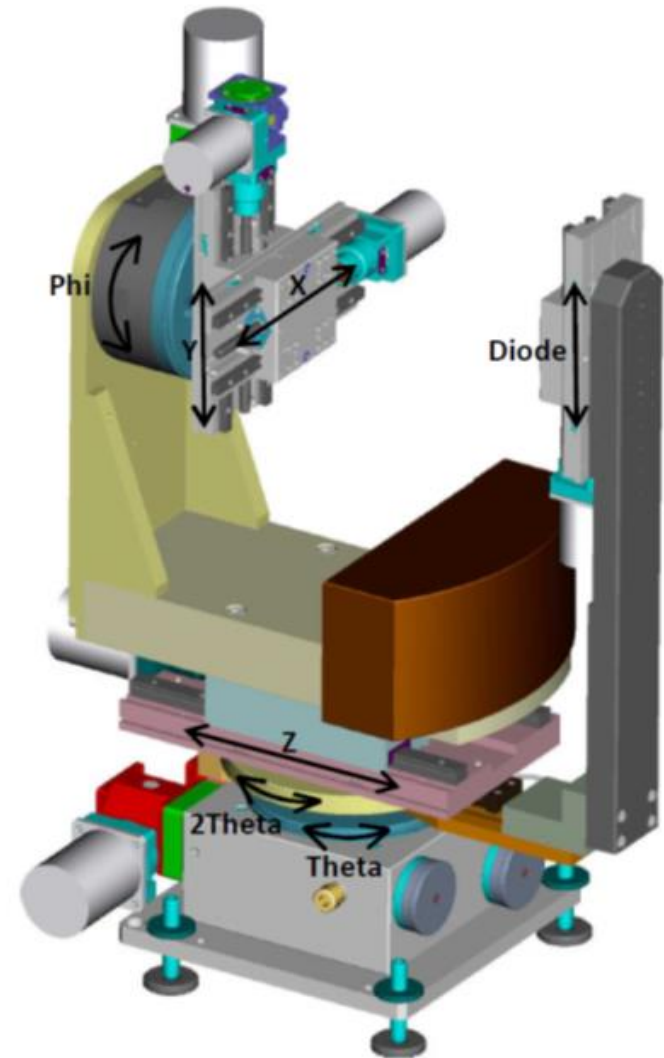
Aiming at moving the sample to be investigated in various directions/ orientations with respect to the exciting X-ray beam or with respect to the detectors.

X-ray Detectors:

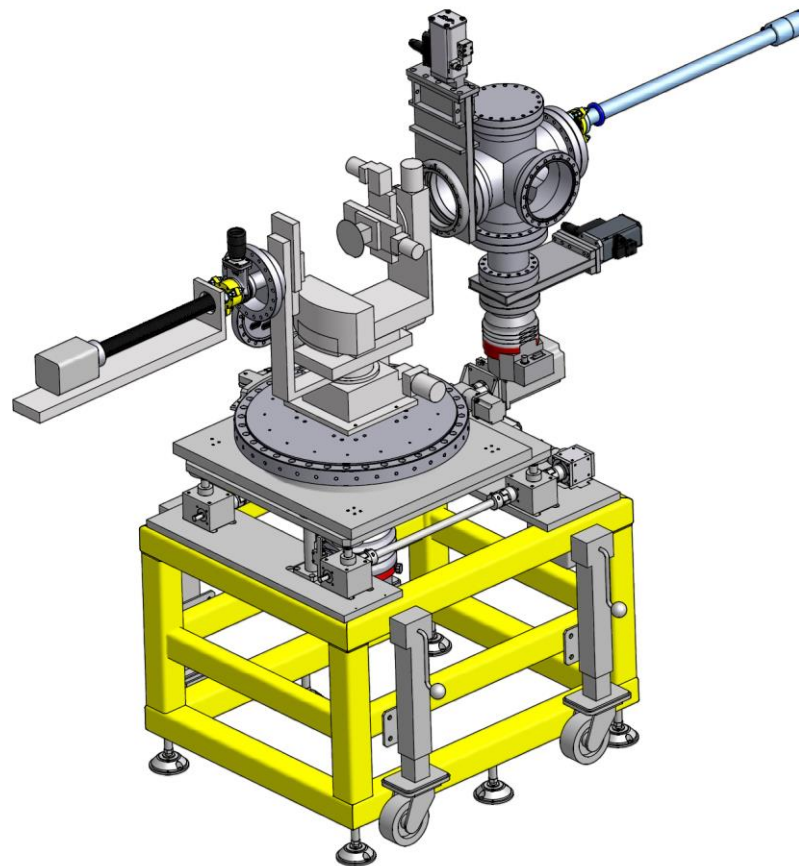
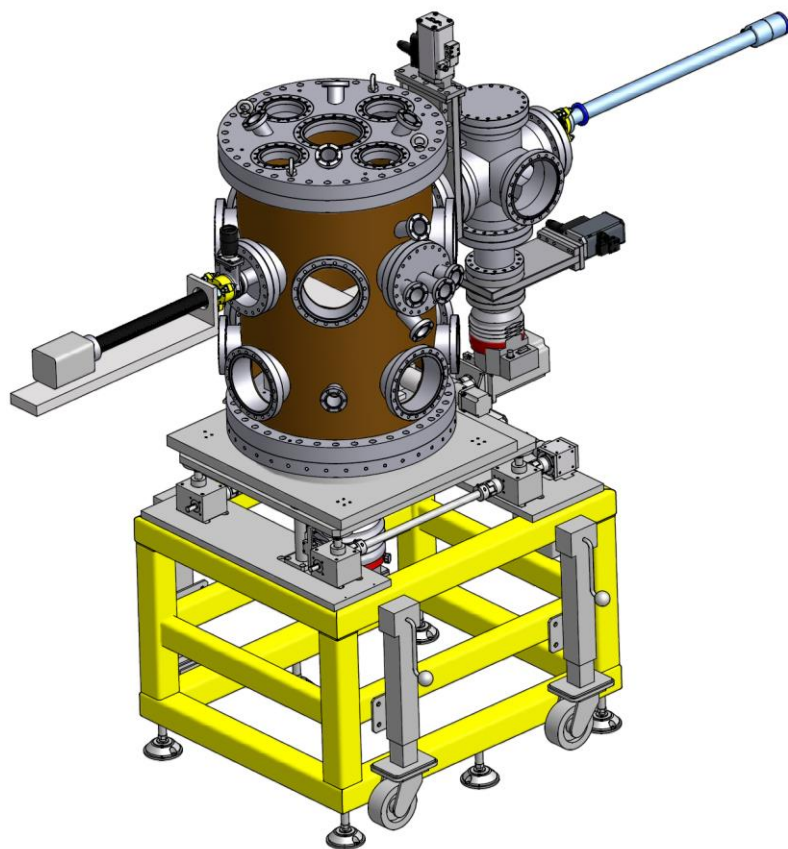
Ultra Thin Window (UTW) Bruker Silicon Drift detector (30 mm², FWHM 130 eV @ Mn-K α), photodiodes and other beam monitoring devices

A high performance x-ray tube was mounted on a flange of the UHVC allowing to use this end-station as a standalone device

The 'Theta' axis would provide an accuracy better than 0.15mrad in the range of -5-110 degrees



The IAEA integrated XRS end station



The IAEA Ultra High Vacuum Chamber (UHVC) is based on a prototype design by Physikalisch - Technische Bundesanstalt (PTB, Berlin)* with the assistance of the the Technical University of Berlin (TUB)

*Janin Lubeck et al, A novel instrument for quantitative nanoanalytics involving complementary X-ray methodologies, Rev. Scientif. Instrum. 84 (2013) 045106-7



XRF Beamline@ Elettra Sincrotrone, Trieste

| | |
|--|---|
| Energy Range (excitation) | 2000 - 14000 eV |
| Beam size (at exit slits) | 250 μm (hor) X 50 μm (vert) |
| Beam divergence (at exit slits) | 0.15 mrad |
| Flux @5.5 keV (2 GeV) or 7 keV (2.4 GeV) | 5 10^9 ph/s (theory) |
| Monochromator | Si (111), InSb, Multilayers |
| Resolving power | DE/E: $1.5 \cdot 10^{-4}$ (Si(111)) |
| Source | Bending Magnet |

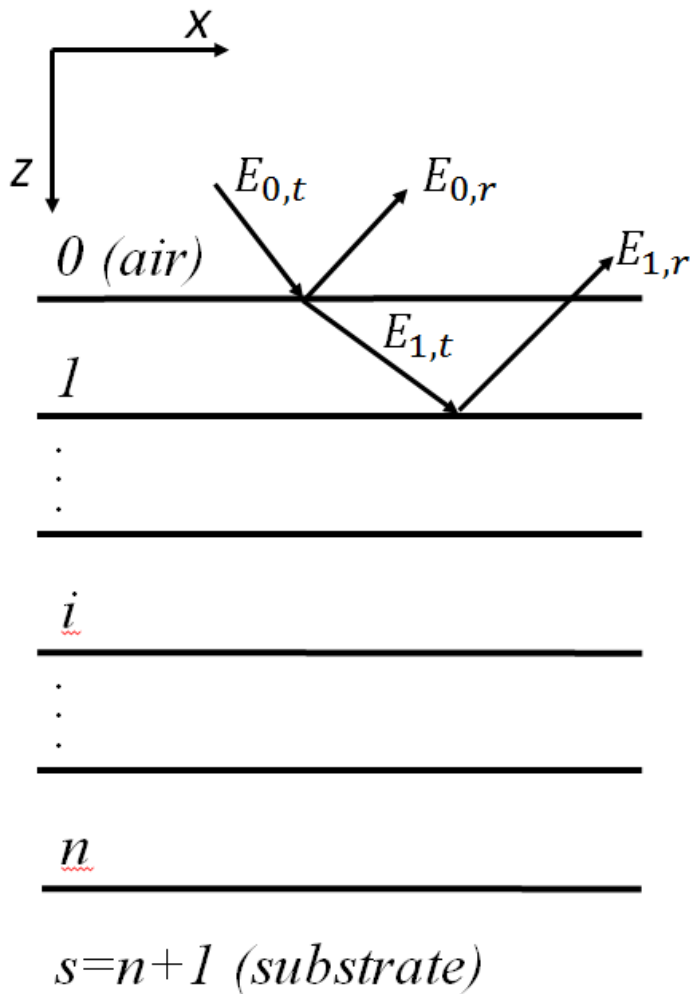
XRF Beamline team: D. Eichert, W. Jark, L. Luhl

Diane.Eichert@Elettra.eu



Elettra Sincrotrone Trieste

Theory (Parratt's formalism)



$$E_j(r) = E_j \exp \left[i \left(\omega \times t - \vec{k}_j \cdot \vec{r} \right) \right]$$

$$k_{j,x} = \frac{2\pi}{\lambda} \cos\theta \quad k_{j,z} = \frac{2\pi}{\lambda} \left(\epsilon_j - \cos^2\theta \right)^{1/2}$$

$$\epsilon_j = n_j^2 \approx 1 - 2\delta_j - i2\beta_j$$

n_j - refractive index can be calculated directly from **Xraylib**:

float **Refractive_Index_Re**(const char compound[], float E, float density)

float **Refractive_Index_Im**(const char compound[], float E, float density)

The sign convention is IMPORTANT!

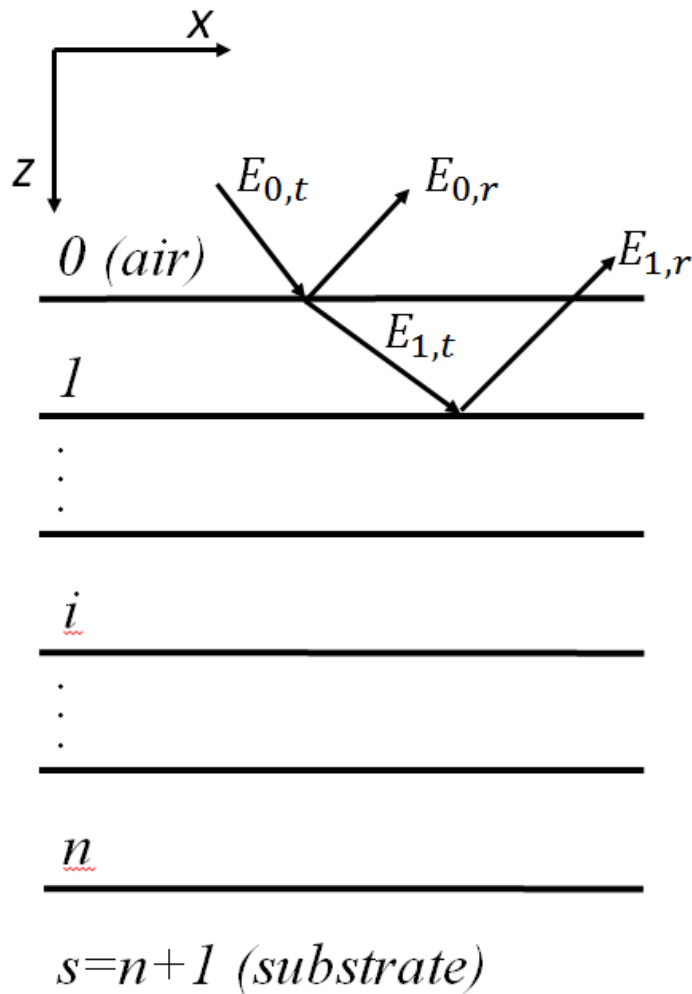
Fresnel coefficients for each interface:

$$r_j = \frac{k_{j,z} - k_{j+1,z}}{k_{j,z} + k_{j+1,z}}$$

$$t_j = \frac{2k_{j,z}}{k_{j,z} + k_{j+1,z}}$$

Schematic diagram for stratified media

Theory (Parratt's formalism)



Recursive method:

The transmitted (E_j^t) and reflected (E_j^r) field amplitudes at the top of layer j

$$E_j^r = a_j^2 X_j E_j^t$$

$$E_{j+1}^t = \frac{a_j E_j^t t_j}{1 + a_{j+1}^2 X_{j+1} r_j}$$

$$X_j = \frac{(r_j + a_{j+1}^2 X_{j+1})}{1 + a_{j+1}^2 X_{j+1} r_j}$$

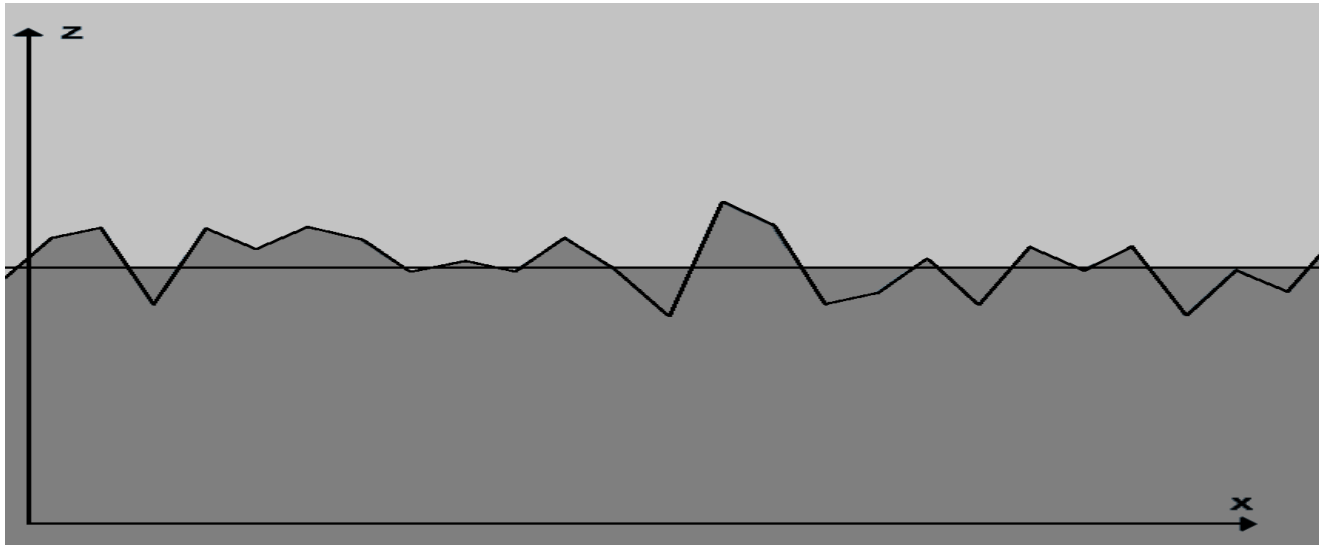
$$a_j = \exp(-ik_{j,z} d_j)$$

The **reflectivity** (R) is found from:

$$R(\theta) = \left| \frac{E_0^r}{E_0^t} \right|^2$$

Schematic diagram for stratified media

Roughness: how to deal with imperfect surfaces?



Debye-Waller approximation: $\tilde{r}_j = r_j S_j$, where $S_j = \exp[-2\sigma_j^2 k_{j,z} k_{j+1,z}]$

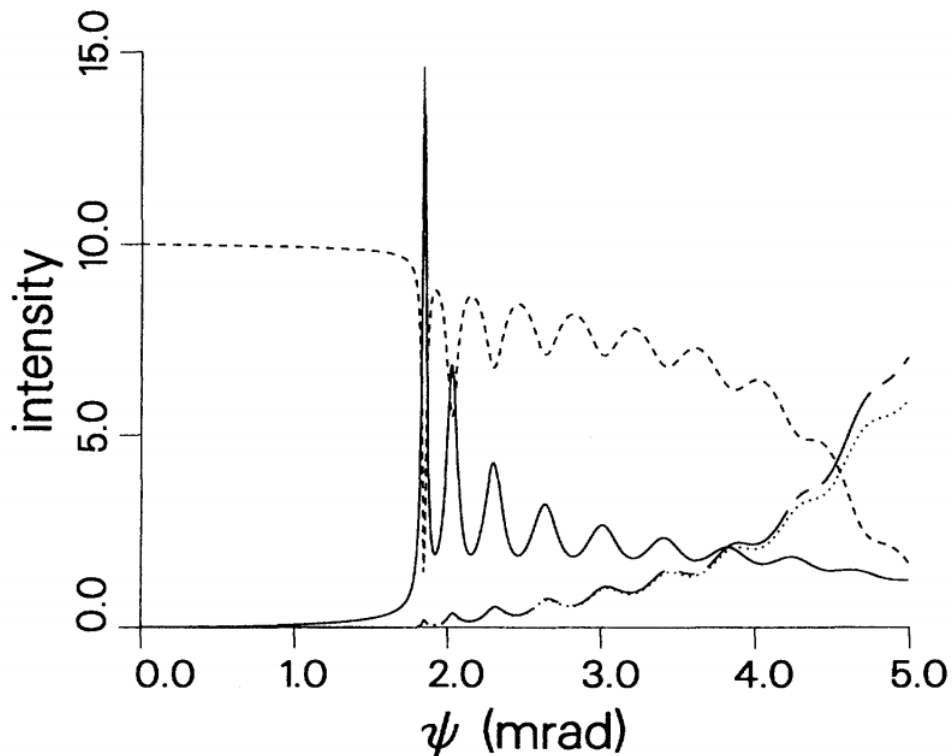
Applicable only to small roughness values (0-2 nm)

Nevot-Croce approximation: $\tilde{r}_j = r_j S_j$ and $\tilde{t}_j = t_j T_j$, where $T_j = \frac{\exp[\sigma_j^2 (k_{j,z} - k_{j+1,z})^2]}{2}$

Fluorescence intensity: element x

$$I_x(\theta) = \sum_i \left(\exp \left[- \sum_{j < i} \frac{(\mu/\rho)_{j,E} \rho_j d_j}{\sin \varphi} \right] \cdot I_{i,x}(\theta) \right)$$

$$I_{j,x}(\theta) = I_0 G S_{x,E_0} \varepsilon_{det} T_{air} \int_0^{d_j} c_x(z) \frac{|E_j^r + E_j^t|^2}{|E_j^t|^2} \exp \left(- \left[\frac{(\mu/\rho)_E}{\sin \varphi} \right] \rho z \right) dz$$



D.K.G. de Boer, *PRB*, **44**, 1991, 498

Differential Evolution is an heuristic optimizer developed by Rainer Storn and Kenneth Price

Storn, R.; Price, K. , *Journal of Global Optimization* **11**, 1997, 341–359

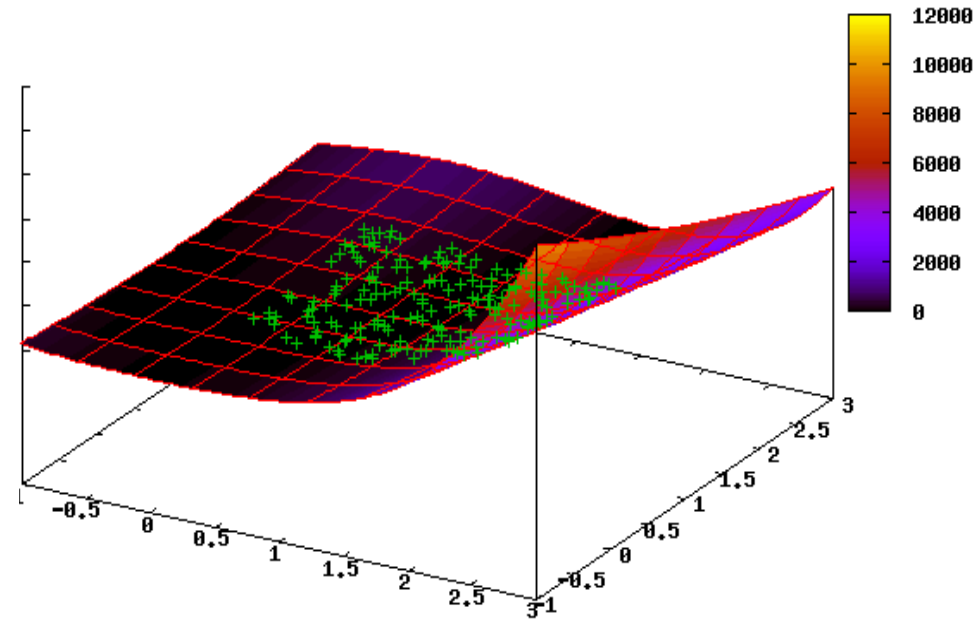
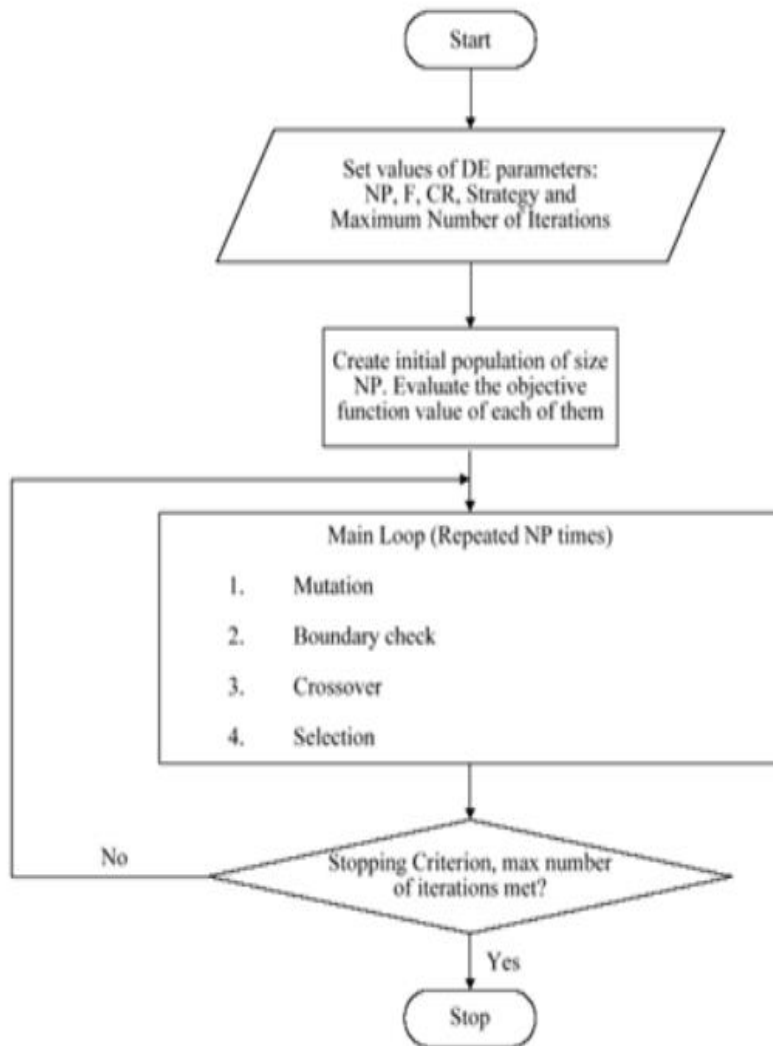
GIXRF/XRR data:

- Many parameters to fit
- Many local minima

Genetic algorithms:

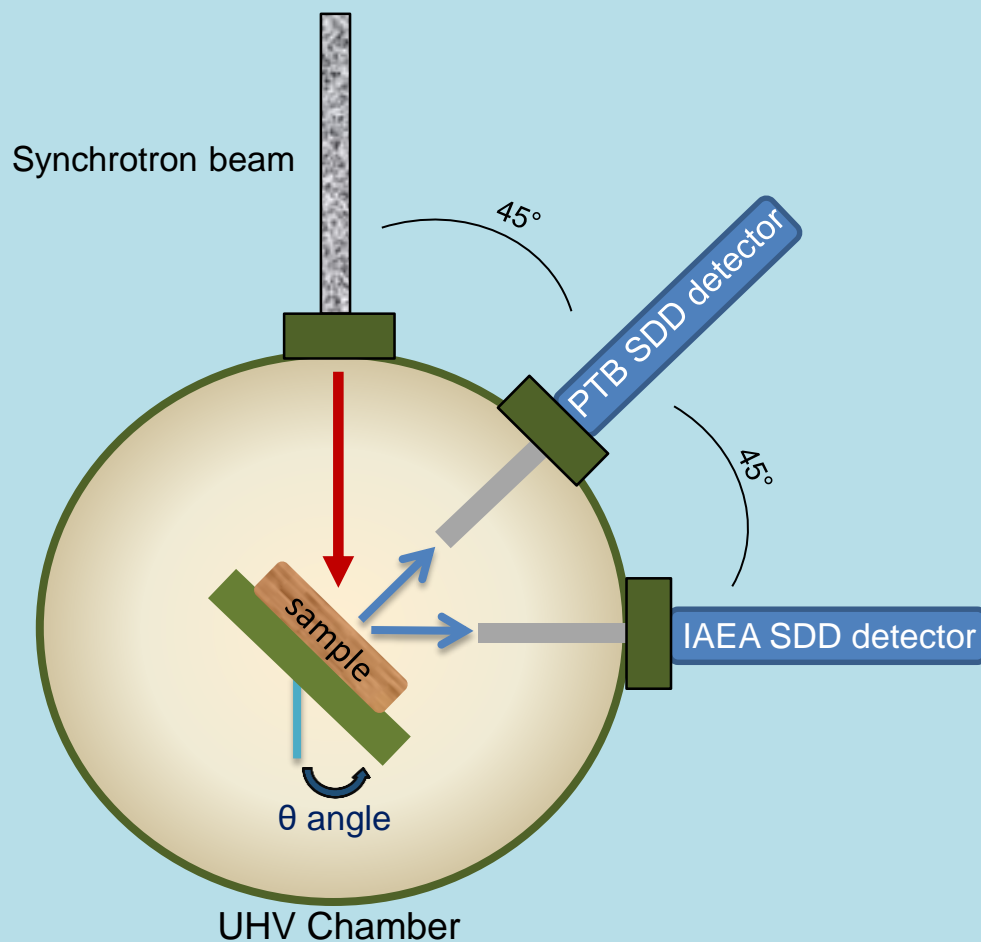
- Allow to find the global minimum
- No need to know derivatives
- The convergence could be unstable (might need more than one run)

Fitting: Differential evolution



**Flow chart of a
DE algorithm**

- First measurements and alignment tests at the PGM beamline of BESSY II
- Experimental setup

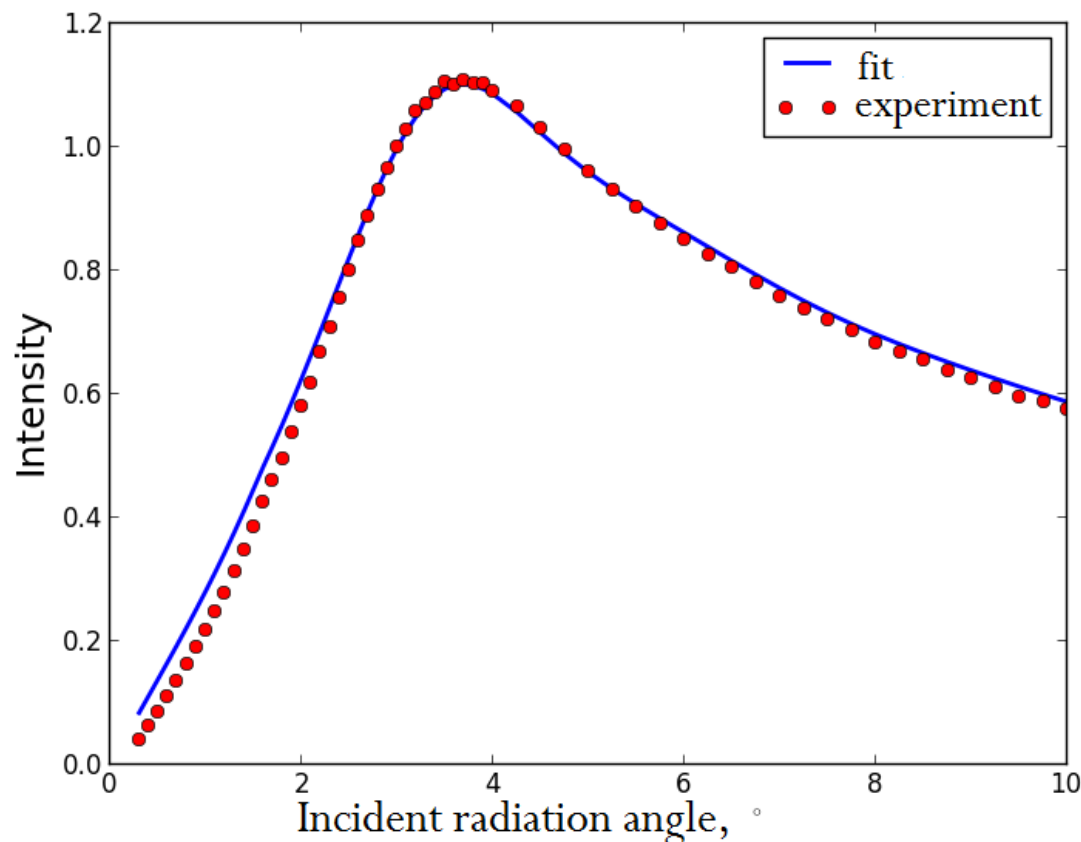
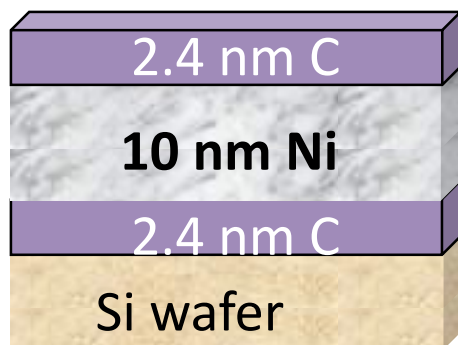


Measurements at conventional XRF geometry and GI conditions (scan of θ angle from 0° to 10°). Distance sample-detector ~ 5 cm. Incident photon energy **1060 eV**

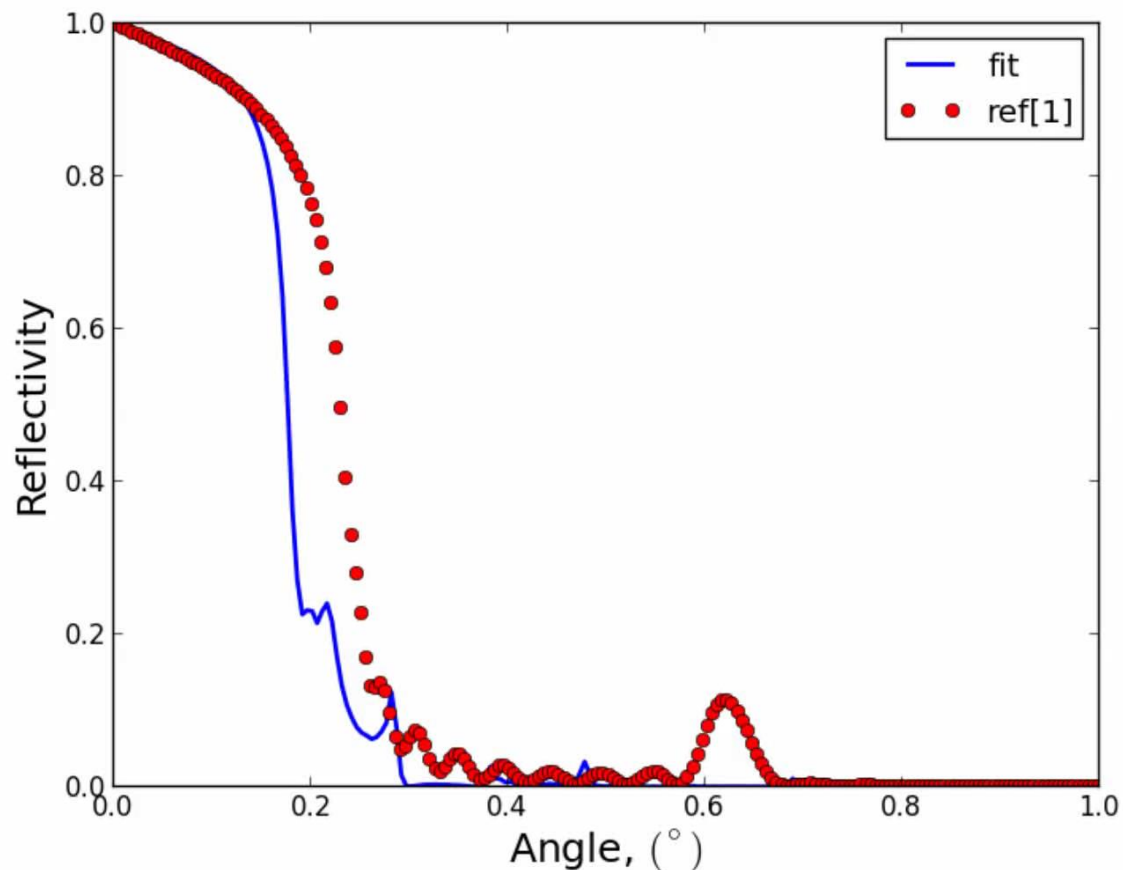


1st phase of commissioning at PTB, May-August 2013

Analysis of stratified nano-structured samples (August 2013)

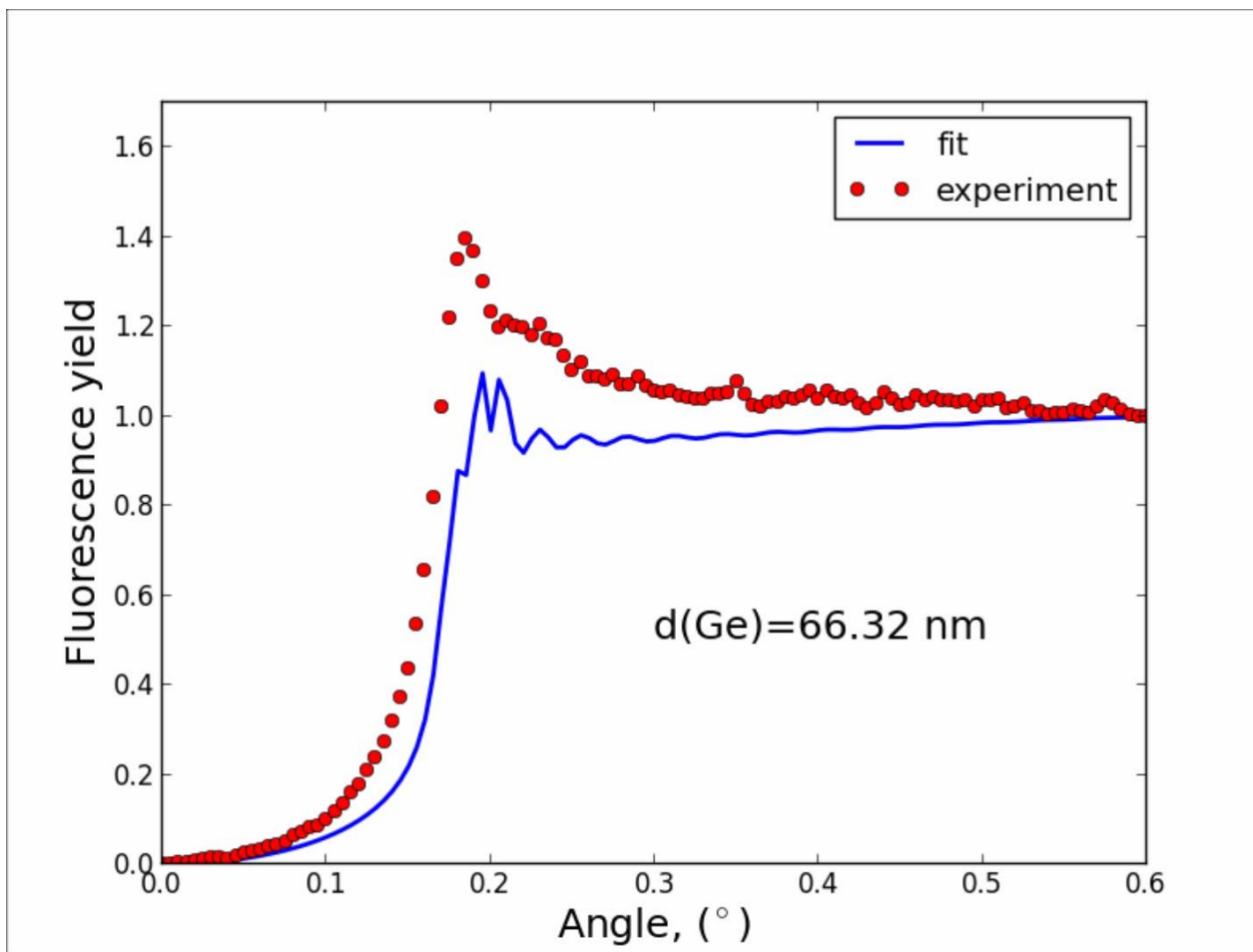


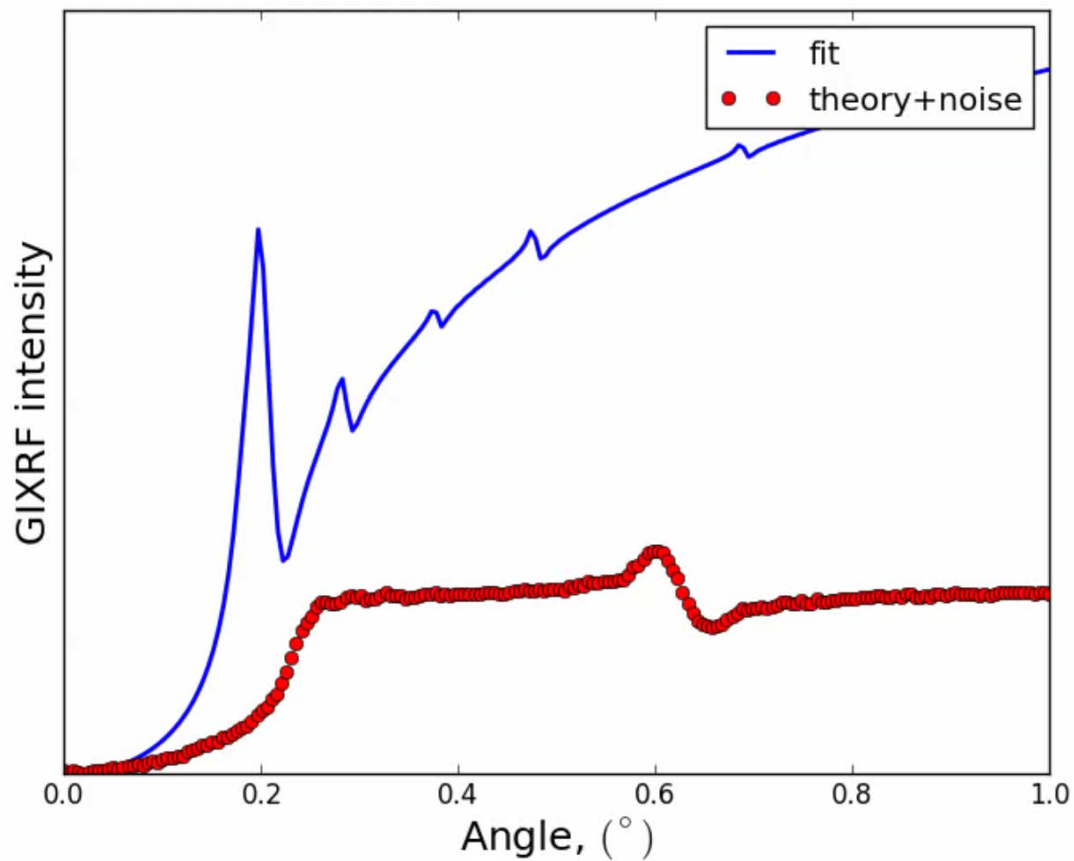
Ni-L line intensity vs incident SR angle (experiment + theory)
(Preliminary results: first GI experiment)



[1] D.K.G. de Boer, *PRB*, **44**, 1991, 498

Example Ge(29 nm)/Si at 15.2 keV

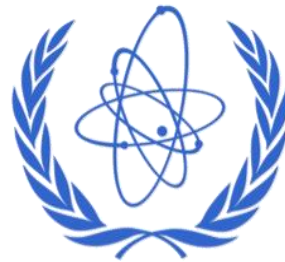




- We used Parratt's recursive algorithm to calculate GIXRF/XRR intensities and DE to fit the experimental data. This allowed us to characterize the first measurements obtained with the new UHVC end-station of IAEA-Elettra
- The results showed an acceptable agreement with the experiment. Further improvements are under development



Thank you for your attention!



IAEA

International Atomic Energy Agency